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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/609,631	07/01/2003	Shingo Ishihara	503.38289CC2	2368
20457	7590 08/09/2005	EXAMINER		
ANTONELLI, TERRY, STOUT & KRAUS, LLP 1300 NORTH SEVENTEENTH STREET			NGUYEN, JOSEPH H	
SUITE 1800 ARLINGTON, VA 22209-3873		-	ART UNIT	PAPER NUMBER
			2815	

DATE MAILED: 08/09/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)	
	10/609,631	ISHIHARA ET AL.	(M
Office Action Summary	Examiner	Art Unit	
	Joseph Nguyen	2815	
The MAILING DATE of this communication Period for Reply	appears on the cover sheet wit	th the correspondence address	s
A SHORTENED STATUTORY PERIOD FOR RETHE MAILING DATE OF THIS COMMUNICATION. Extensions of time may be available under the provisions of 37 CF after SIX (6) MONTHS from the mailing date of this communication. If the period for reply specified above is less than thirty (30) days, and If NO period for reply is specified above, the maximum statutory period for reply within the set or extended period for reply will, by some Any reply received by the Office later than three months after the meaned patent term adjustment. See 37 CFR 1.704(b).	ON. R 1.136(a). In no event, however, may a rent. a reply within the statutory minimum of thirty- griod will apply and will expire SIX (6) MON tatute, cause the application to become AB.	eply be timely filed y (30) days will be considered timely. THS from the mailing date of this commun ANDONED (35 U.S.C. § 133).	nication.
Status			
 Responsive to communication(s) filed on 1 This action is FINAL 2b) Since this application is in condition for all closed in accordance with the practice und 	This action is non-final. Dwance except for formal matte	•	rits is
Disposition of Claims			
4) ☐ Claim(s) 1,2,4-6 and 8-11 is/are pending in 4a) Of the above claim(s) is/are with 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1,2,4-6 and 8-11 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and subject to restriction an	drawn from consideration.		
Application Papers			
9)☑ The specification is objected to by the Exam 10)☑ The drawing(s) filed on 01 July 2003 is/are: Applicant may not request that any objection to Replacement drawing sheet(s) including the co 11)☐ The oath or declaration is objected to by the	a)⊠ accepted or b)⊡ object the drawing(s) be held in abeyan rrection is required if the drawing(ce. See 37 CFR 1.85(a). s) is objected to. See 37 CFR 1.	
Priority under 35 U.S.C. § 119			
 12) Acknowledgment is made of a claim for force a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document * See the attached detailed Office action for a 	nents have been received. nents have been received in Appriority documents have been reau (PCT Rule 17.2(a)).	pplication No. <u>09/526,557</u> . received in this National Stag	e
Attachment(s)	🗖		
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SE Paper No(s)/Mail Date 	Paper No(s	ummary (PTO-413))/Mail Date formal Patent Application (PTO-152) 	

DETAILED ACTION

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Specification

The specification is objected to as failing to provide proper antecedent basis for the claimed subject matter. See 37 CFR 1.75(d)(1) and MPEP § 608.01(o). Correction of the following is required: the limitation "wherein the at least one gate electrode is above or beneath the semiconductor layer containing the gate insulating film" in claim 8 is not defined in the originally filed disclosure. Note that only "the at least one gate electrode is beneath the semiconductor layer contacting the gate insulating film" is defined as shown in figure 1(a) of the instant application.

Double Patenting

The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. See *In re Goodman*, 11 F.3d 1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970); and, *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent is shown to be commonly owned with this application. See 37 CFR 1.130(b).

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

Claims 1-2, 4-6 and 8-11 are rejected under the judicially created doctrine of obviousness-type double patenting as being unpatentable over claims 1-7 of U.S. Patent No. 6,593,977 B2 in view of Tanaka et al. (US 5,892,244).

Regarding claim 1, claims 1 and 3 of U.S. Patent No. 6,593,977 B2 disclose all the structure set forth in the claimed invention except said semiconductor layer being located so as to contact said gate insulating film only at regions acting as channel regions of the IC card apparatus. However, Tanaka et al. discloses in figure 3 said semiconductor layer 4 (col. 4, lines 38-39) being located so as to contact said gate insulating film 3 (col. 4, line 35) only at regions acting as channel regions of the IC card apparatus. In view of such teaching, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify claims 1 and 3 of U.S. Patent No. 6,593,977 B2 by having said semiconductor layer being located so as to contact said gate insulating film only at regions acting as channel regions of the IC card apparatus to highly modulate a current flowing between the source and drain with a gate voltage (col. 3, lines 10-11, Tanaka et al.).

Regarding claim 2, claim 2 of U.S. Patent No. 6,593,977 B2 discloses the semiconductor layer is an organic semiconductor layer.

Regarding claim 4, claim 4 of U.S. Patent No. 6,593,977 B2 discloses the substrate is a plastic substrate.

Regarding claim 5, claim 5 of U.S. Patent No. 6,593,977 B2 discloses the plastic substrate is made of polymer material.

Regarding claim 6, claim 6 of U.S. Patent No. 6,593,977 B2 discloses the channel region has a size which is a same size as a gate electrode of the at least one gate electrode.

Regarding claim 11, claims 1 and 7 of U.S. Patent No. 6,593,977 B2 disclose all the structure set forth in the claimed invention except said semiconductor layer being located so as to contact said gate insulating film only at regions acting as channel regions of the IC card apparatus. However, Tanaka et al. discloses in figure 3 said semiconductor layer 4 (col. 4, lines 38-39) being located so as to contact said gate insulating film 3 (col. 4, line 35) only at regions acting as channel regions of the IC card apparatus. In view of such teaching, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify claims 1 and 7 of U.S. Patent No. 6,593,977 B2 by having said semiconductor layer being located so as to contact said gate insulating film only at regions acting as channel regions of the IC card apparatus to highly modulate a current flowing between the source and drain with a gate voltage (col. 3, lines 10-11, Tanaka et al.).

Regarding claim 8, Tanaka et al. discloses in figure 3 the channel regions are between respective source and drain electrodes 5, 6 (col. 4, lines 34-36) of the at least one source electrode and the at least one drain electrode, wherein the respective source and drain electrodes contact opposite ends of the semiconductor layer 4 contacting the gate insulating film 3, and wherein the at least one gate electrode 2 (col. 4, line 22) is beneath the semiconductor layer contacting the gate insulating film.

Regarding claim 9, claim 6 of U.S. Patent No. 6,593,977 B2 discloses the channel region has a size which is a same size as a gate electrode of the at least one gate electrode.

Regarding claim 10, claim 2 of U.S. Patent No. 6,593,977 B2 discloses the semiconductor layer is an organic semiconductor layer.

Response to Arguments

Applicant's arguments with respect to claims 1-2, 4-6 and 8-11 have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Joseph Nguyen whose telephone number is (571) 272-1734. The examiner can normally be reached on Monday-Friday, 7:30 am- 4:30 pm. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached on (571) 272-1664. The fax phone number for the organization where this application or proceeding is assigned is (571) 273-8300 for regular communications.

Application/Control Number: 10/609,631

Art Unit: 2815

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

JN August 4, 2005

> TOM THOMAS SUPERVISORY PATENT EXAMINER

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